L Number	Hits	Search Text	DB	Time stamp
1	3	4222345.pn.	USPAT;	2003/08/11 08:4
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
2	2	3939798.pn.	USPĀT;	2003/08/11 08:4
		•	US-PGPUB;	
į			EPO; JPO;	
			DERWENT;	
			IBM TDB	
3	5	(("3664295") or ("3636916") or ("3608519") or ("2456708") or ("2391595")).PN.	USPĀT	2003/08/11 08:4
4	11	"3,939,798"	USPAT;	2003/08/11 09:0
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM TDB	
5	270	(119/719 cole or 156/345 31 cole or 156/345 32 cole) and (jet or normal)	USPAT;	2003/08/11 09:3
?	2/0	(118/719.ccls. or 156/345.31.ccls. or 156/345.32.ccls.) and (jet or nozzle)	US-PGPUB;	2003/08/11 09:
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	2222 /22 /24 22
ó	1	((jet or nozzle) same plasma) and bernouli	USPAT;	2003/08/11 09:
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
7	3	((jet or nozzle) and plasma) and bernouli	USPĀT;	2003/08/11 09:
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM TDB	
3 .	5	plasma and bernouli	USPĀT;	2003/08/11 09:
´	,		US-PGPUB;	20037 007 11 07.
			EPO; JPO;	.9
			DERWENT;	14
			-	1 .
,	2275	_1	IBM_TDB USPAT;	2003/08/11 (3):
'	3375	plasma and vortex		2003/08/11 09:
			US-PGPUB;	
-	-	- - ,	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
.0	262	(plasma and vortex) and ((stage or support or platen or table or susceptor or	USPAT;	2003/08/11 09:
		chuck or holder or mandrel) with (wafer or substrate))	US-PGPUB;	-
			EPO; JPO;	
			DERWENT;	
			IBM TDB	
1	9	(plasma and vortex) and ((stage or support or platen or table or susceptor or	USPĀT;	2003/08/11 09:
		chuck or holder or mandrel) with article) not ((plasma and vortex) and ((stage or	US-PGPUB;	Í
		support or platen or table or susceptor or chuck or holder or mandrel) with	EPO; JPO;	
		(wafer or substrate)))	DERWENT;	
		("	IBM TDB	
12	3	(("6203661") or ("6095582") or ("6040548")).PN.	USPĀT	2003/08/11 09:
3	23	(plasma or vortex) and bernouli	USPAT;	2003/08/11 09:
.5	23	(plasma or voices) and bernoun	US-PGPUB;	2003/ 00/ 11 0/.
			EPO; JPO;	
-				
İ			DERWENT;	
	22		IBM_TDB	2002 (00 (44 00
4	23	(plasma or vortex) and bernouli not ((plasma and vortex) and ((stage or support	USPAT;	2003/08/11 09:
		or platen or table or susceptor or chuck or holder or mandrel) with (wafer or	US-PGPUB;	
		substrate)))	EPO; JPO;	
			DERWENT;	
			IBM_TDB	1
15	4331	((vortex or bernouli) same (stage or support or platen or table or susceptor or	USPĀT;	2003/08/11 10:
ŀ		chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or	US-PGPUB;	İ
		platen or table or susceptor or chuck or holder or mandrel) with (wafer or	EPO; JPO;	
		substrate)))	DERWENT;	
		. v mar v m mar v 111		

Search History 8/11/03 1:28:19 PM Page 1 C:\APPS\EAST\Workspaces\08860763.wsp

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16	575	(((vortex or bernouli) same (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or subtrates))) and (plasma or ionings)	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/08/11 10:0
17	133	substrate)))) and (plasma or ioniz\$5) zervigon.xa.	IBM_TDB USPAT; US-PGPUB;	2003/08/11 10:1
			EPO; JPO; DERWENT; -IBM_TDB	
18	421	((((vortex or bernouli) same (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or substrate)))) and (plasma or ioniz\$5)) and (wafer or substrate or article or work or	USPĀT; US-PGPUB; EPO; JPO; DERWENT;	2003/08/11 10:4
19	1802	semiconductor) ((vortex or bernouli) with (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or substrate)))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/11 10:4
20	1761	(((vortex or bernouli) with (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or substrate)))) not (((((vortex or bernouli) same (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or substrate)))) and (plasma or ioniz\$5)) and (wafer or substrate or article or work or semiconductor))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/11 10:-
21	487	((((vortex or bernouli) with (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or substrate)))) not (((((vortex or bernouli) same (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or substrate)))) and (plasma or ioniz\$5)) and (wafer or substrate or article or work or semiconductor))) and (wafer or substrate or article or work or semiconductor)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/11 11:
22	5	279/\$.ccls. and (bernouli or vortex)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/08/11 11:
23	0	"bernouli chuck"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/08/11 11:
24	1166	(((vortex or bernouli) with (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or substrate)))) and @ay<1996	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/08/11 11:
25	860	((((vortex or bernouli) with (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or substrate)))) and @ay<1996) not (((((vortex or bernouli) with (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or substrate)))) not (((((vortex or bernouli) same (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or substrate)))) and (plasma or ioniz\$5)) and (wafer or substrate or article or work or semiconductor))) and (wafer or substrate or article or work or semiconductor))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/11 11:

(heraruli or vordex) as wood

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26	271	(((((vortex or bernouli) with (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or	USPAT; US-PGPUB; EPO; JPO;	2003/08/11 11:5
		substrate)))) and @ay<1996) not (((((vortex or bernouli) with (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder	DERWENT; IBM_TDB	
		or mandrel) with (wafer or substrate)))) not (((((vortex or bernouli) same (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or		
		chuck or holder or mandrel) with (wafer or substrate)))) and (plasma or ioniz\$5))— and (wafer or substrate or article or work or semiconductor))) and (wafer or		
27	39	substrate or article or work or semiconductor))) and (jet or nozzle) (((((vortex or bernouli) with (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or substrate)))) and @ay<1996) not (((((vortex or bernouli) with (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/08/11 12:0
		vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or substrate)))) not (((((vortex or bernouli) same (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or substrate)))) and (plasma or ioniz\$5)) and (wafer or substrate or article or work or semiconductor))) and (wafer or substrate or article or work or semiconductor))) and plasma	-	
28	252	((((((vortex or bernouli) with (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or substrate)))) and @ay<1996) not (((((vortex or bernouli) with (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or substrate)))) not (((((vortex or bernouli) same (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/11 12:0
		((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or substrate)))) and (plasma or ioniz\$5)) and (wafer or substrate or article or work or semiconductor))) and (wafer or substrate or article or work or semiconductor))) and (jet or nozzle)) not ((((((vortex or bernouli) with (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or		a. -
		substrate)))) and @ay<1996) not (((((vortex or bernouli) with (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or substrate)))) not ((((vortex or bernouli) same (stage or support or platen or table or susceptor or chuck or holder or mandrel)) not ((plasma and vortex) and ((stage or support or platen or table or susceptor or chuck or holder or mandrel) with (wafer or substrate)))) and (plasma or ioniz\$5)) and (wafer or substrate or article or work or semiconductor))) and (wafer or		
-	8424	substrate or article or work or semiconductor))) and plasma) 118/715.ccls. or 118/728.ccls. or 118/50.ccls. or 156/345.29.ccls. or 156/345.33.ccls. or 156/345.34.ccls. or 156/345.35.ccls. or 156/345.36.ccls. or 156/345.26.ccls. or 156/345.51.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/08/11 08:3
-	7990	137/262-264.ccls. or 137/454.2 or 137/560.ccls. or 137/561r.ccls. or 137/561a.ccls. or 137/571-576.ccls. or 137/590.ccls. or 137/594-596.ccls. or 137/599.01.ccls. or 137/599.05-599.07.ccls. or 137/602.ccls.	USPĀT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/08/10 16:3
-	2239	141/285-286.ccls. or 141/37.ccls. or 141/44-47.ccls. or 141/54.ccls. or 141/301-302.ccls. or 141/367.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/08/10 16:3
-	453	261/127.ccls. or 261/131.ccls. or 261/146-147.ccls. or 261/150.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/08/10 16:3

•	2567	261/19-22.ccls. or 261/23.1.ccls. or 261/40.ccls. or 261/42.ccls. or	USPAT;	2003/08/10 16:35
		261/62-63.ccls.	US-PGPUB; EPO; JPO; DERWENT; IBM TDB	
-	6993	261/64.1.ccls. or 261/65.ccls. or 261/75-76.ccls. or 261/94-96.ccls. or 261/100-102.ccls. or 261/105.ccls. or 261/108-109.ccls. or 261/113.ccls. or 261/114.1.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/10 16:35
	28016	(118/715.ccls. or 118/728.ccls. or 118/50.ccls. or 156/345.29.ccls. or 156/345.33.ccls. or 156/345.34.ccls. or 156/345.35.ccls. or 156/345.36.ccls. or 156/345.36.ccls. or 156/345.36.ccls. or 156/345.36.ccls. or 156/345.26.ccls. or 156/345.26.ccls. or 137/560.ccls. or 137/561.ccls. or 137/561.ccls. or 137/571-576.ccls. or 137/590.ccls. or 137/594.596.ccls. or 137/599.01.ccls. or 137/599.05-599.07.ccls. or 137/602.ccls.) or (141/285-286.ccls. or 141/37.ccls. or 141/44-47.ccls. or 141/301-302.ccls. or 141/367.ccls.) or (261/127.ccls. or 261/131.ccls. or 261/146-147.ccls. or 261/150.ccls.) or (261/19-22.ccls. or 261/23.1.ccls. or 261/40.ccls. or 261/42.ccls. or 261/62-63.ccls.) or (261/64.1.ccls. or 261/65.ccls. or 261/75-76.ccls. or 261/94-96.ccls. or 261/100-102.ccls. or 261/105.ccls. or 261/108-109.ccls. or 261/113.ccls. or 261/114.1.ccls.)	USPĀT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/10 16:35
-	8	((118/715.ccls.) or 118/728.ccls. or 118/50.ccls. or 156/345.29.ccls. or 156/345.33.ccls. or 156/345.34.ccls. or 156/345.35.ccls. or 156/345.36.ccls. or 156/345.36.ccls. or 156/345.26.ccls. or 156/345.36.ccls. or 156/345.26.ccls. or 156/345.26.ccls. or 137/560.ccls. or 137/560.ccls. or 137/561.ccls. or 137/571-576.ccls. or 137/590.ccls. or 137/594-596.ccls. or 137/599.01.ccls. or 137/599.05-599.07.ccls. or 137/602.ccls.) or (141/285-286.ccls. or 141/37.ccls. or 141/44-47.ccls. or 141/54.ccls. or 141/301-302.ccls. or 141/367.ccls.) or (261/127.ccls. or 261/131.ccls. or 261/146-147.ccls. or 261/150.ccls.) or (261/19-22.ccls. or 261/23.1.ccls. or 261/40.ccls. or 261/42.ccls. or 261/62-63.ccls.) or (261/100-102.ccls. or 261/105.ccls. or 261/108-109.ccls. or 261/113.ccls. or 261/113.ccls. or 261/114.1.ccls.)) and planetary and (boat or carrier) and (plasma or ion)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/10 16:36